

Fraunhofer Group for Microelectronics in Cooperation with the Leibniz Institutes FBH and IHP

## **Optoelectronic Systems**

## Research Fab Microelectronics Germany: Benefit from Europe's Largest R&D Cooperation for Micro- and Nanoelectronics

The Research Fab Microelectronics Germany (FMD) is a multisite cooperation advancing micro- and nanoelectronics research and development and comprises eleven institutes of the Fraunhofer Group for Microelectronics, as well as the two Leibniz institutes FBH and IHP. We are a One-Stop-Shop for cuttingedge R&D services, application solutions and new technologies for a wide range of industrial customers.

By joining forces, we are able to provide tailor made technology and system solutions from a single source. Drawing on FMD's broad technology portfolio, we have established six technology platforms: Microwave and Terahertz, Power Electronics, Extended CMOS, Optoelectronic Systems, Sensor Systems, and MEMS Actuators. Together these bundle the necessary individual expertise – from system design to testing and reliability assessment – to meet customer needs. Apart from leveraging synergies between technological know-how and the development of technological innovation, the platforms prioritize close cooperation with customers throughout the development process and the bundling of technological competencies along the entire value chain.

#### **Our Technology Portfolio**



**Extended CMOS** Design, fabrication and system integration of CMOS circuits.



**Microwave and Terahertz** Cutting-edge devices and circuit for frequencies up to and including the THz range.



#### **Power Electronics** Design and fabrication of power electronic devices, including integ-

ration in modules and systems.



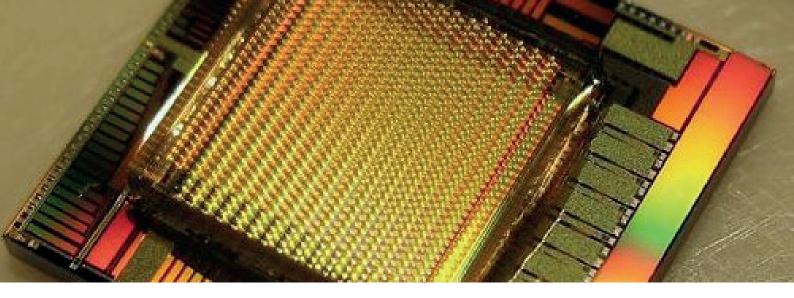




#### **Optoelectronic Systems** Fully integrated optoelectronic systems for image acquisition and processing, and communication up to Tbit/s speed.



MEMS Actuators Design and fabrication, as well as characterization, testing and system integration of MEMS actuators.



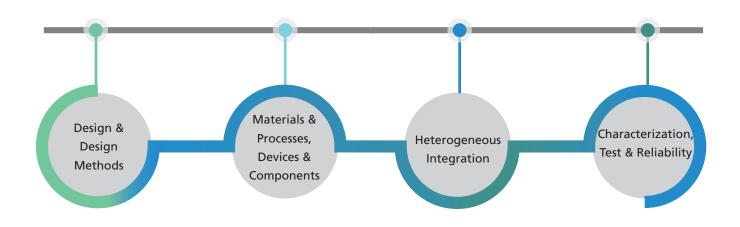
#### **Technology Platform: Optoelectronic Systems**

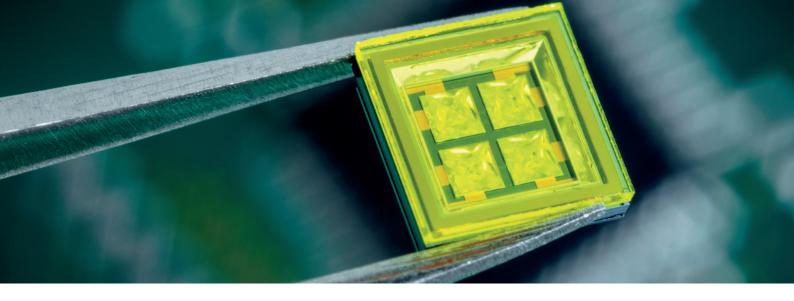
The technology platform Optoelectronic Systems combines the broad, interdisciplinary engineering expertise of Research Fab Microelectronics Germany (FMD) to achieve leading-edge optoelectronic devices and systems. Applications include imaging acquisition and processing, communication up to Tbit/s speed, and optical sensing applications. Our one-stop shop covers the complete component and technology chain for optical communication, from emitter, to modulator and receiver, through to fully integrated optoelectronic systems.

Starting with the specification and design of single devices, we integrate optoelectronic circuits and even design and realize complete hybrid-integrated systems. We lend our long-term experience and comprehensive know-how to the processing of a variety of materials – from Si to compound semiconductors and polymers – in our cleanroom facilities, as well as using the wide range of heterogeneous integration technologies required to realize even the most complex systems. Our Si-, III-V-, and polymer-based technologies allow the manufacturing of active and passive structures, like optical filters and multiplexers or lasers, semiconductor optical amplifiers (SOAs), and gain chips. We have a wide ranging portfolio of active devices for different operation wavelengths, such as GaAs-based devices (wavelength between 626 nm and 1180 nm), InP-based devices

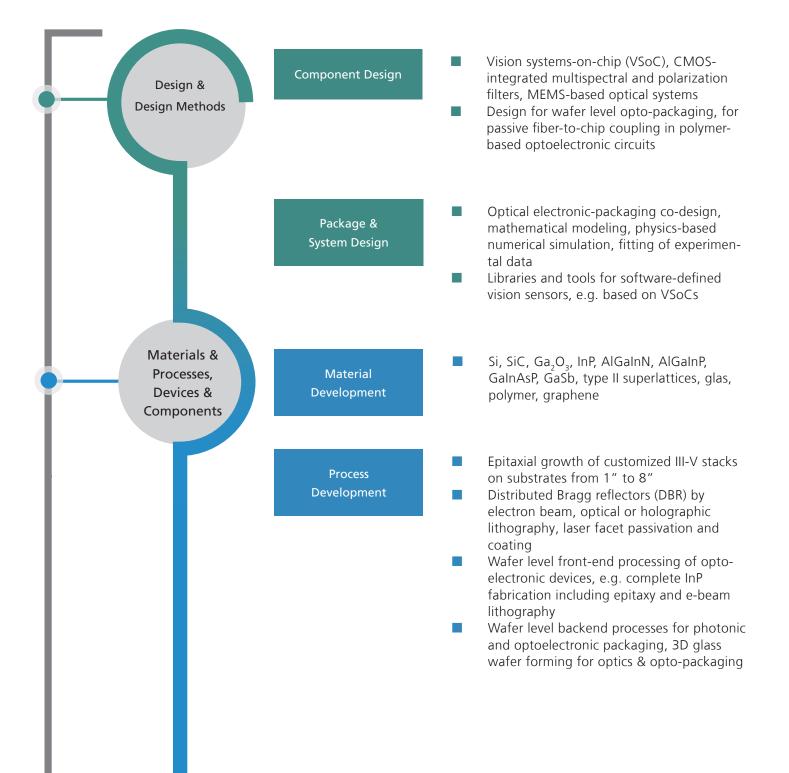
(~ 1.25 – 1.7  $\mu$ m), and quantum cascade devices (~ 2 – 11  $\mu$ m). To reach all wavelengths from the yellow to the UV region of the optical spectrum non-linear frequency conversion can be harnessed. All the components and heterogeneous integration technologies – from emitters to fully-integrated modulators through to receivers – are available to design customized optoe-lectronic systems.

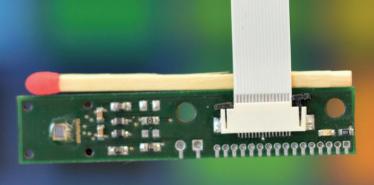
Our expertise in heterogeneous integration technologies illustrates the multitude of technological solutions at our disposal: systems-on-chip (SoC), advanced packaging, wafer level capping, and advanced substrate/interposer technologies. Furthermore, the hybrid integration of active III-V materials in polymer- and Si-based technology, including wafer-level atomic layer deposition for encapsulation, plays a significant role in achieving complete hybrid photonic integrated circuits (hybrid PICs). We perform in-depth characterization of the electro-optic performance of the designed, manufactured, and assembled optoelectronic systems and test the latter using multiple stress scenarios (thermal and mechanical stress), as well as performing reliability and degradation assessments. Finally, we also make customized solutions for specific applications possible by identifying the optimal materials and technologies required.

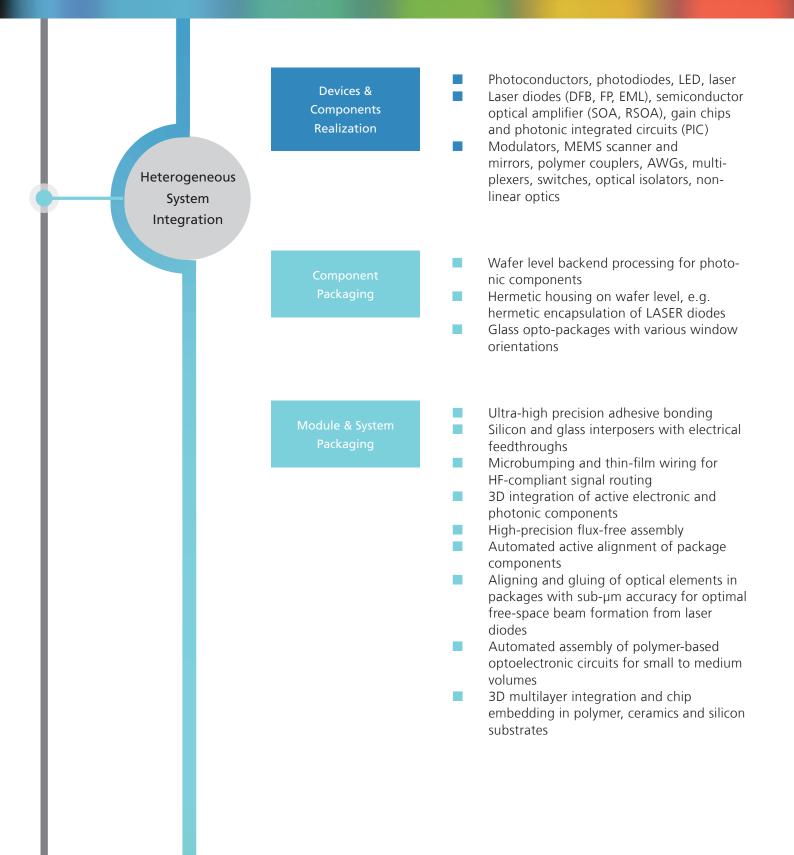




### Our Competencies in Optoelectronic Systems along the Value Chain

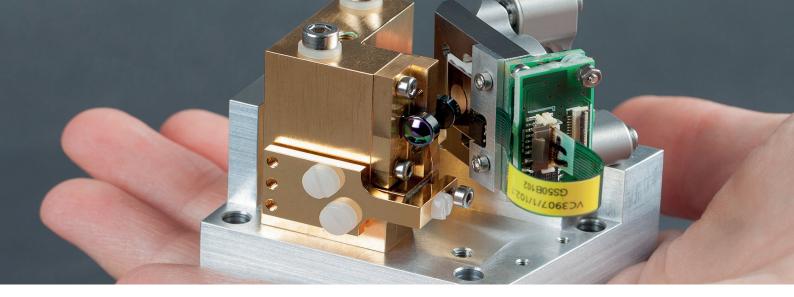






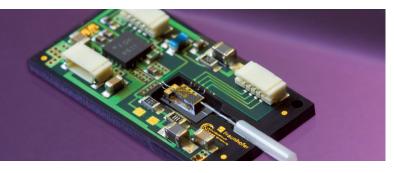


| Characterization,  | Material<br>Characterization                         | - | Characterization of optical materials used<br>for both passive and active components,<br>such as complex layer stacks  |
|--------------------|--|---|--|
| Test & Reliability | Process<br>Characterization                          |   | Analysis of gluing strategies and geome-<br>tries (UV and thermal epoxies)<br>Design of laser-based processing and<br>fusing of glass components<br>In-line process monitoring and SPC for<br>InP-based device processing  |
|                    | Devices &<br>Components Charac-<br>terization & Test |   | Full characterization of optoelectronic<br>devices<br>In-depth characterization of application-<br>specific performance parameters for<br>optical and optoelectronic components<br>and systems<br>Measurement of spectral and propagation<br>properties of diverse light sources<br>Inspection of coupling interfaces to<br>photonic integrated circuits<br>Characterization of micro-optical<br>components with wave front sensors<br>Characterization of spectral and polariza-<br>tion properties of image sensors down to<br>pixel level<br>High-resolution and time-resolved<br>characterization of pixel cells<br>Accelerated lifetime testing and failure<br>analysis |
|                    | System Test &<br>Reliability                         | ł | Reliability testing (thermal cycling,<br>thermal storage)<br>System test beds for optoelectronic<br>components   |



#### Technology Example: Tunable Laser Module

The combined expertise of Fraunhofer HHI and IZM makes customer-specific miniaturized optoelectronic systems available for a broad range of application fields. The example board shown in the image below was developed for the German telecommunication vendor ADVA Optical Networking SE and comprises an integrated tunable laser chip based on Fraunhofer HHI's photonic integration technology. The integrated tunable laser combines an



InP-based active section, which allows 10 Gb/s direct modulation for data transmission, and a polymer-based passive section featuring a phase shifter and a tunable Bragg grating, which achieve a wavelength tunability of 20 nm in the C band. The integrated tunable laser was assembled on an electronic board designed and fabricated by Fraunhofer IZM. With novel technologies developed by Fraunhofer IZM, fabricating a robust 3D substrate, as well as integrating SMD and optoelectronic components, is achievable. The silica-filled epoxy resin board is manufactured using compression molding and is compatible with standard SMT processes, allowing it to be processed like a common PCB.

Integrated tunable laser chip employing Fraunhofer HHI's photonic integration technology and assembled on an electronic board designed and fabricated by Fraunhofer IZM.

### Technology Example: External Cavitiy Quantum Cascade Lasers

Quantum cascade laser (QCLs) harness intersubband transitions in the conduction band of a semiconductor layer structure. Such laser sources are used in real-time spectroscopy, which facilitates fast quality and process control and the development of mobile or even handheld devices. With sophisticated layer design, they can be optimized for performance or wide wavelength tunability. The emission wavelength of the chip material can be adjusted in external resonators using a diffraction grating. Micro-opto-electro-mechanical systems (MO-EMS) grating scanners are used for this purpose.

Resonant grating scanners track a sinusoidal trajectory and allow very for high spectral scanning speeds of up to 1 kHz. With quasi-static grating scanners, individual wavelengths can be specifically targeted and almost any desired trajectory can be traced, thus enabling arbitrary spectral scanning speeds with repetition rates of up to several 10 hertz. They can replace conventional external cavity (EC) QCLs in many applications, with the added advantages of significantly smaller size and increased

functionality. Fraunhofer IAF builds highly integrated EC QCLs for the mid-infrared wavelength regime that combine unique spectral scanning speeds with the small footprint mentioned above.

Scanning MOEMS grating module.



# Research Fab Microelectronics Germany (FMD)

The Research Fab Microelectronics Germany (FMD) as a cooperation of the Fraunhofer Group for Microelectronics with the Leibniz Institutes FBH and IHP is your central contact for all questions concerning micro- and nanoelectronics in Germany and Europe. As a One-Stop-Shop, FMD combines the scientifically excellent technologies, applications and system solutions of the cooperating institutes into a combined overall offer in order to actively address the current and future challenges of electronics research. Under the virtual roof of FMD, Europe's largest R&D cooperation has been created, which, with its 2,000 researchers and its unique diversity of competencies and infrastructures, provides customers and partners with easy access to new applications and high technologies at different technical levels of maturity. The FMD offers a comprehensive and Europe-wide unique range of services for companies, especially for small and medium-sized enterprises (SMEs) but also start-ups, and is an important innovation driver and strategic dialog partner.

In this way, the Research Fab Microelectronics Germany strengthens the competitiveness of Germany as a microelectronics location and ensures further technological sovereignty along the entire value chain. Together with its international partners from science and industry, FMD also actively contributes to the German and European research agenda, thereby providing important impetus for the development of elementary innovations for the world of tomorrow – to the benefit of society and the strengthening of the German and European economy.

## A cooperation of









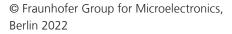


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